

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

DEOK-HYEON CHOE et al.

Serial No.: *to be assigned*

Examiner: *to be assigned*

Filed: 18 April 2001

Art Unit: *to be assigned*

For: TENSION MASK FOR COLOR CRT, METHOD FOR MANUFACTURING THE
TENSION MASK, AND EXPOSURE MASK USED IN THE MANUFACTURE
OF THE TENSION MASK

INFORMATION DISCLOSURE STATEMENT

Assistant Commissioner
for Patents
Washington, D.C. 20231

Sir:

In accordance with 37 C.F.R. §1.56, and §§1.97 and 1.98 as amended, Applicant cites,
provides copies and discusses the following art references:

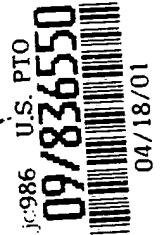
	<u>Patent No.</u>	<u>Inventor</u>	<u>Date</u>
•	4,942,332	Adler et al.	7/90
•	4,926,089	Moore	5/90

Adler et al.'332 discloses tied slit mask for color cathode ray tubes.

Moore'089 discloses tied slit foil shadow mask with false ties.

The citation of the foregoing references is not intended to constitute an assertion that other

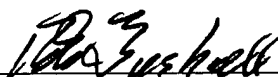
PATENT
P56342



or more relevant art does not exist. Accordingly, the Examiner is requested to make a wide-ranging and thorough search of the relative arts.

No fee is incurred by this Statement.

Respectfully submitted,



Robert E. Bushnell

Reg. No.: 27,774

1522 "K" Street, N.W., Suite 300
Washington, D.C. 20005
Area Code: 202-408-9040

Folio: P56342
Date: 18 April 2001
I.D.: REB/sb